

Reference No.: KP2974

Dispatch No.: 253459 1/

Dispatch Date: July 20, 2004

Notification of Reason(s) for Refusal

Patent Appln. No.: JP2002-258690
Drafting Date: July 8, 2004
Examiner of JPO: Masanori Suzuki
Applicant/Representative: Mutsuyasu YANASE
Applied Provision: Patent Law Section 29 (1) and (2)

This application should be refused for the reason mentioned below. If the applicant has any argument against the reason, such argument should be submitted within 60 days from the dispatch date of this notification.

Reason

1 The invention(s) in Claims 3, 4, 7, 10, 16, 19, 25, 43, and 46 of the subject application should not be granted under Patent Law Section 29(1)(iii) since it is an invention(s) described in the publication 1 mentioned below which was distributed in Japan or foreign countries or an invention (s) known to the public through telecommunications lines prior to the filing of the subject application.

2 The invention(s) in Claims 3, 4, 7, 11 - 13, 16, 19-22, 25, 31, 34, 43, and 46 of the subject application should not be granted under Patent Law Section 29(2) since it could have easily been made by persons who have common knowledge in the technical field to which the invention(s) pertains, on the basis of the invention(s) described in the publications 1 - 4 mentioned below which was distributed in Japan or foreign countries prior to the filing of the subject application.

Note (See the list of cited documents etc., below.)

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Remark:

In the cited document 1. a metric material for an electronic component for wiring patterns, said metric material including mainly Cu and also 0.3 to 3% by weight of Cr, Ta, and Ti and 0.3 to 3 % by weight of Ag and Cu as a remaining content, is described.

It is ordinary to form an electrical component having a wiring pattern by an etching process using a solution including phosphoric acid and nitric acid, an etching process under a gas atmosphere including chlorine, or an etching process under a gas atmosphere including fluorine (refer to cited documents 2, 3 and 4). Thus, it is perceived that a person skilled in the art could have easily made an invention to apply these etching processes to the invention in the cited document 1.

For the claims other than the claims specified in this notification of reasons for refusal, no reason for refusal is found at present. If any reasons for refusal is found later, it will be notified.

The list of cited documents etc.

1. JP 2002-75101
2. JP 2002-9061
3. JP 2002-198352
4. JP 2002-237484

Record of the result to prior art search

Technical field(s) to be searched: Int.Cl(7) C22C 9/00
C23F 1/00, 4/00

This record is not a component(s) of the reason(s) for refusal.